



# MODEL 1061

## SEM Mill

A state-of-the-art ion milling and polishing system. It is compact, precise, and consistently produces high-quality scanning electron microscopy (SEM) samples in the shortest amount of time for a wide variety of applications.

### Model 1061 SEM Mill specifications

#### Ion sources

Two TrueFocus ion sources  
Variable energy (100 eV to 10.0 keV) operation  
Beam current density up to 10 mA/cm<sup>2</sup>  
Milling angle range of 0 to +10°  
Choice of single or dual ion source operation  
Manual or motorized (optional) ion source angle adjustment  
Independent ion source energy control  
Adjustable spot size  
Faraday cups for the direct measurement of beam current from each ion source; allows optimization and adjustment of the ion source parameters for specific applications

#### Sample stage

Sample size:

- Cross section\*  
Maximum: 10 x 10 x 4.0 mm [0.39 x 0.39 x 0.157 in.]  
Minimum: 3 x 3 x 0.7 mm [0.12 x 0.12 x 0.028 in.]
- Planar  
32 mm diameter x 25 mm height [1.25 x 1 in.]

Automatic sample thickness sensing to establish the milling plane and maximize throughput  
360° sample rotation with variable rotation speed  
Sample rocking  
Magnetic encoder provides absolute positioning accuracy

#### User interface

Instrument operation controlled via 254 mm [10 in.], ergonomically adjustable touch screen

\* Standard size; other sizes available upon request.

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<b>Vacuum system</b>	Turbomolecular drag pump and an oil-free, multi-stage diaphragm pump Vacuum sensing with a cold cathode, full-range gauge
<b>Process gas</b>	UHP argon (99.999%); nominal 15 psi delivery pressure required Automatic gas control using two mass flow controllers
<b>Automatic termination</b>	Automatic termination by time or temperature
<b>In situ viewing and imaging</b>	Sample can be monitored in situ in the milling position when using either the stereo or the high-magnification microscope  Viewing window protected by a programmable shutter that prevents buildup of sputtered material and preserves the ability to observe the sample in situ
<b>Sample cooling (optional)</b>	Liquid nitrogen conductive cooling with integral dewar and automatic temperature interlocks  Dewar access positioned close to instrument operator  Ability to program and maintain a specific temperature between ambient and cryogenic  Choice of: <ul style="list-style-type: none"> <li>• Standard dewar capacity (3 to 5 hours of cryo conditions)</li> <li>• Extended dewar capacity (12+ hours of cryo conditions)</li> </ul>
<b>Vacuum or inert gas transfer capsule (optional)</b>	Allows transfer or storage of a sample at vacuum or in an inert gas environment
<b>Cross-section station (optional)</b>	Produces pristine cross-section samples  Samples are secured to the mask by an adhesive  Allows precise positioning of the area of interest – X, Y, and  Effective for use with a wide variety of materials, including semiconductor devices, multilayers, ceramics, and hard/brittle materials  Prepared region of interest is flat and free from damage for subsequent SEM imaging and analysis  Accommodates a wide range of sample and mask sizes: <ul style="list-style-type: none"> <li>• Sample and mask align both laterally and angularly</li> <li>• Multiple uses from a single mask</li> </ul>

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**Clamping cross-section station** (optional)

Produces pristine cross-section samples

Ideal for samples that can be damaged by exposure to adhesives; samples are secured via a clamping mask, without adhesives

Allows precise positioning of the area of interest – X, Y, and

Effective for use with a wide variety of materials, including semiconductor devices, multilayers, ceramics, and hard/brittle materials

Prepared region of interest is flat and free from damage for subsequent SEM imaging and analysis

Accommodates a wide range of sample and mask sizes:

- Sample and mask align both laterally and angularly
- Multiple uses from a single mask

**Stack light** (optional)

Stack light indicator for determining milling operations status from a distance

**Microscope** (optional)

Load lock window accommodates the following microscopes:

- 7 to 45X stereo microscope attachment for direct specimen observation
- 525X high-magnification microscope and CMOS (complementary metal oxide semiconductor) camera system for site-specific image acquisition and display
- 1,960X high-magnification microscope and CMOS camera system for site-specific image acquisition and display

**Sample illumination**

Both the high-magnification and stereo microscopes have light sources that provide top-down, user adjustable, reflected sample illumination

**Enclosure**

Width (includes room on either side for service access: 127 cm [50 in.]

Height:

- Minimum height (without microscope or stack light options): 61 cm [32 in.]
- Maximum height (with stack light option): 77 cm [38 in.]

Depth (includes room for service access and exhaust fan air flow): 102 cm [40 in.]

Enclosure design offers easy access to internal components when performing maintenance tasks

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<b>Weight</b>	73 kg [161 lb.]
<b>Power</b>	100/120/220/240 VAC, 50/60 Hz, 720 W
<b>Warranty</b>	One year
<b>Service contracts</b>	Contact <a href="mailto:sales@fischione.com">sales@fischione.com</a> for pricing



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